

Dialog DataStar[options](#)[logoff](#)[feedback](#)[help](#)[databases](#)[search
page](#)

Titles

To view one or many selected titles scroll down the list and click the corresponding boxes. Then click display at the bottom of view one particular document click the link above the title to display immediately.

[order](#)

Documents 1 to 18 of 18 from your search **hexachlorodisilane**:

- ☐ **Select All**
- ☐ 1 [display full document](#)
2002. (INZZ) Lateral over-growth of 3C-SiC on patterned Si(111) substrates.
- ☐ 2 [display full document](#)
2000. (INZZ) Selective epitaxial growth of silicon carbide on patterned silicon substrates using **hexachlorodisilane** and propane.
- ☐ 3 [display full document](#)
2000. (INZZ) Film properties of low-k silicon nitride films formed by **hexachlorodisilane** and ammonia.
- ☐ 4 [display full document](#)
1999. (INZZ) Low-k SiN film for Cu interconnects integration fabricated by ultra low temperature thermal CVD.
- ☐ 5 [display full document](#)
1997. (INZZ) Raman and infrared vibrational spectra, normal coordinate analysis and ab initio calculations of 1,1,2,2-tetrachlorodisilane and ab initio calculations of **hexachlorodisilane**.
- ☐ 6 [display full document](#)
1996. (INZZ) Growth of cubic SiC on Si substrate by CVD using hexamethyldisilane and **hexachlorodisilane**.
- ☐ 7 [display full document](#)
1994. (INZZ) Deposition of niobium silicide thin films from **hexachlorodisilane** and niobium pentachloride.
- ☐ 8 [display full document](#)
1989. (INZZ) **Hexachlorodisilane** as a precursor in the LPCVD of silicon dioxide and silicon oxynitride films.
- ☐ 9 [display full document](#)
1988. (INZZ) LPCVD of silicon nitride films from **hexachlor disilane** and ammonia.
- ☐ 10 [display full document](#)
1989. (INZZ) Single crystal growth of Cr/sub 3/Si and Cr/sub 5/Si/sub 3/ using in- situ CVD process.
- ☐ 11 [display full document](#)
1987. (INZZ) Chemical vapor deposition of silicon films using **hexachl rodisilane**.

☐ 12 [display full document](#)

1987. (INZZ) Vapour-phase siliconizing of iron plate and crystal growth of FeSi/sub 2/ using Si/sub 2/Cl/sub 6/ as a source of silicon.

☐ 13 [display full document](#)

1987. (INZZ) Vapour-phase siliconizing of some nickel-base alloys and transition metals using Si/sub 2/Cl/sub 6/ as a source of silicon.

☐ 14 [display full document](#)

1986. (INZZ) Deposition and microhardness of SiC from the Si/sub 2/Cl/sub 6/-C/sub 3/H/sub 8/-H/sub 2/-Ar system.

☐ 15 [display full document](#)

1985. (INZZ) NQR /sup 35/Cl spectra of perchloropolysilanes.

☐ 16 [display full document](#)

1978. (INZZ) The Raman and infrared spectrum of hexachlorodisilazane.

☐ 17 [display full document](#)

1973. (INZZ) The molecular structure of **hexachlorodisilane**.

☐ 18 [display full document](#)

1969. (INZZ) **Hexachlorodisilane**: vibrational spectrum, structure and internal rotation.

Display Format	Display in	ERA SM Electronic Redistribution & Archiving
<input checked="" type="radio"/> Full <input type="radio"/> Free <input type="radio"/> Short <input type="radio"/> Medium <input type="radio"/> Custom Help with Formats	<input checked="" type="radio"/> HTML <input type="radio"/> Tagged (for tables)	Copies you will redistribute: <input type="text"/> Employees who will access archived record(s): <input type="text"/> Help with ERA
		Publication year YYYY <input type="text"/> <input type="button" value="v"/> Ascending <input type="button" value="v"/>

[order](#)[Top - News & FAQs - Dialog](#)

© 2002 Dialog